

# New Frontiers in the Future of Plasma Processing: Where We Are and What Lies Ahead

Panel Discussion, October 26, 2023--- 12 pm PST 7pm UTC

Free Registration: <https://conta.cc/3RZD2uq>



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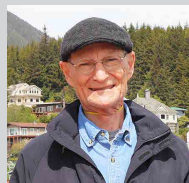
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Jianping Zhao, Ph.D.  
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Daphne Pappas, Ph.D.  
Director R&D, Plasmatreat, USA  
Moderator



Daniel L. Flamm, Ph.D., J.D.  
CEO, Microtechnology Law  
Moderator

Renowned experts discuss the state of art in plasma processing including high & low pressure processing, advanced plasma excitation & reactor control, & tools & requirements for leading edge devices. Other topics include plasma-assisted deposition & etching of advanced films & new materials, plasmas for atomic layer deposition & etching, very fine line plasma etching & deposition, fundamental limits of processing, & evolving applications.

**The Plasma Applications Group of the No. California Chapter  
American Vacuum Society (NCAVS)**